

Silicon N-channel dual-gate MOS-FETs

BF998; BF998R

FEATURES

- Short channel transistor with high forward transfer admittance to input capacitance ratio
- Low noise gain controlled amplifier up to 1 GHz.

APPLICATIONS

- VHF and UHF applications with 12 V supply voltage, such as television tuners and professional communications equipment.

DESCRIPTION

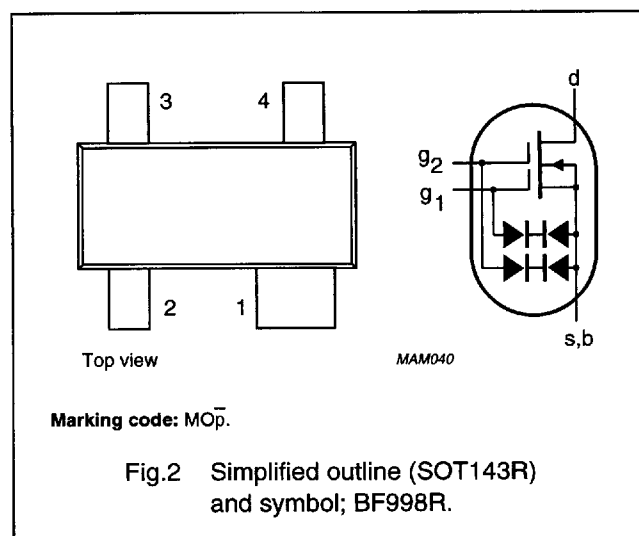
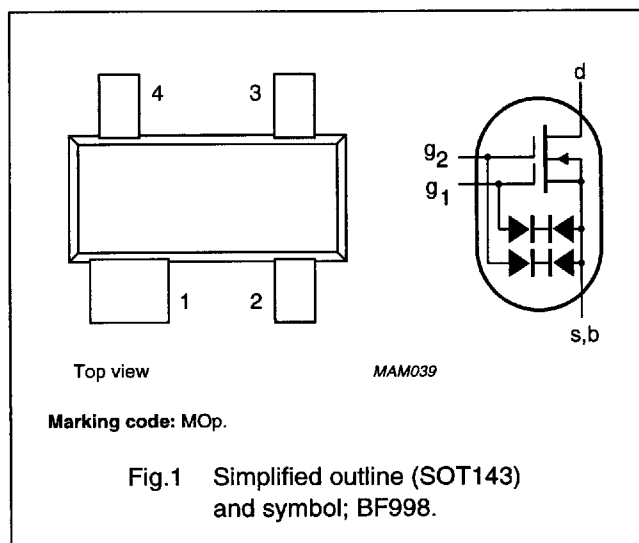
Depletion type field effect transistor in a plastic microminiature SOT143 or SOT143R package with source and substrate interconnected. The transistors are protected against excessive input voltage surges by integrated back-to-back diodes between gates and source.

CAUTION

The device is supplied in an antistatic package. The gate-source input must be protected against static discharge during transport or handling.

PINNING

PIN	SYMBOL	DESCRIPTION
1	s, b	source
2	d	drain
3	g_2	gate 2
4	g_1	gate 1



QUICK REFERENCE DATA

SYMBOL	PARAMETER	CONDITIONS	TYP.	MAX.	UNIT
V_{DS}	drain-source voltage		—	12	V
I_D	drain current		—	30	mA
P_{tot}	total power dissipation		—	200	mW
$ y_{fs} $	forward transfer admittance		24	—	mS
C_{ig1-s}	input capacitance at gate 1		2.1	—	pF
C_{rs}	reverse transfer capacitance	$f = 1 \text{ MHz}$	25	—	fF
F	noise figure	$f = 800 \text{ MHz}$	1	—	dB
T_j	operating junction temperature		—	150	°C

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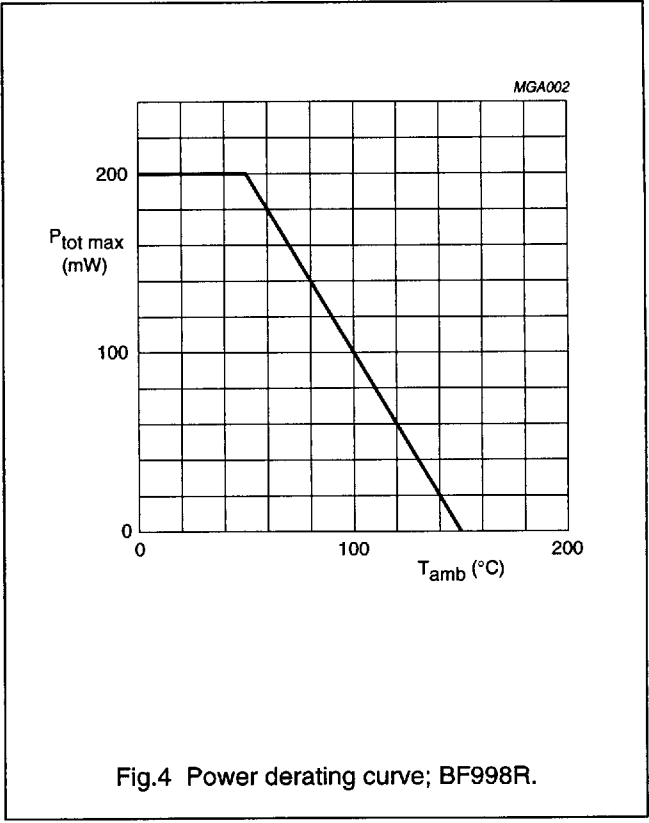
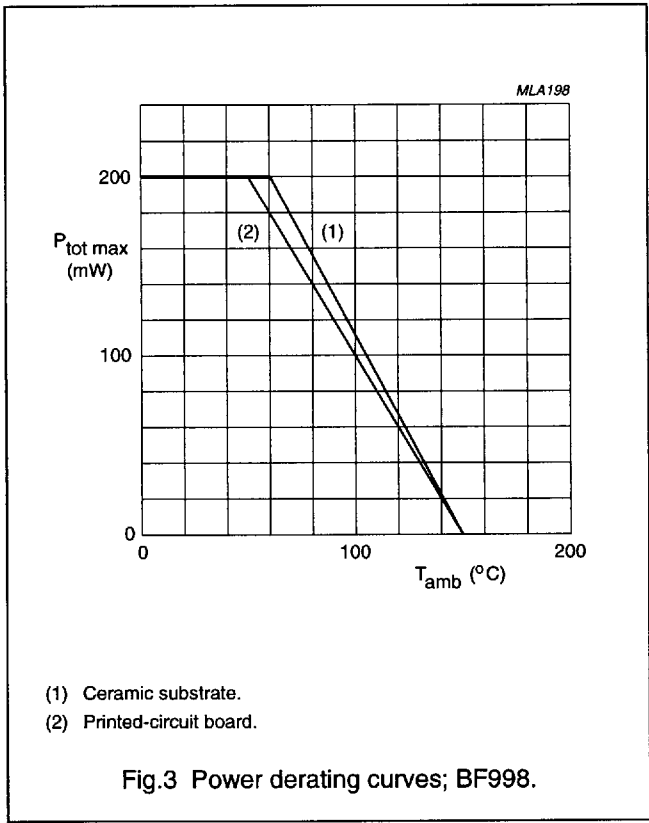
LIMITING VALUES

In accordance with the Absolute Maximum Rating System (IEC 134).

SYMBOL	PARAMETER	CONDITIONS	MIN.	MAX.	UNIT
V_{DS}	drain-source voltage		–	12	V
I_D	drain current		–	30	mA
$\pm I_{G1}$	gate 1 current		–	10	mA
$\pm I_{G2}$	gate 2 current		–	10	mA
P_{tot}	total power dissipation; BF998	up to $T_{amb} = 60\text{ }^{\circ}\text{C}$; see Fig.3; note 1	–	200	mW
		up to $T_{amb} = 50\text{ }^{\circ}\text{C}$; see Fig.3; note 2	–	200	mW
P_{tot}	total power dissipation; BF998R	up to $T_{amb} = 50\text{ }^{\circ}\text{C}$; see Fig.4; note 1	–	200	mW
T_{stg}	storage temperature		–65	+150	$^{\circ}\text{C}$
T_j	operating junction temperature		–	150	$^{\circ}\text{C}$

Notes

1. Device mounted on a ceramic substrate, 8 mm × 10 mm × 0.7 mm.
2. Device mounted on a printed-circuit board.



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THERMAL CHARACTERISTICS

SYMBOL	PARAMETER	CONDITIONS	VALUE	UNIT
$R_{th\ j-a}$	thermal resistance from junction to ambient in free air; BF998	note 1	460	K/W
		note 2	500	K/W
$R_{th\ j-a}$	thermal resistance from junction to ambient in free air; BF998R	note 1	500	K/W

Notes

1. Device mounted on a ceramic substrate, 8 mm × 10 mm × 0.7 mm.
2. Device mounted on a printed-circuit board.

STATIC CHARACTERISTICS

 $T_j = 25\ ^\circ\text{C}$; unless otherwise specified.

SYMBOL	PARAMETER	CONDITIONS	MIN.	MAX.	UNIT
$\pm V_{(BR)G1-SS}$	gate 1-source breakdown voltage	$V_{G2-S} = V_{DS} = 0$; $I_{G1-SS} = \pm 10\ \text{mA}$	6	20	V
$\pm V_{(BR)G2-SS}$	gate 2-source breakdown voltage	$V_{G1-S} = V_{DS} = 0$; $I_{G2-SS} = \pm 10\ \text{mA}$	6	20	V
$-V_{(P)G1-S}$	gate 1-source cut-off voltage	$V_{G2-S} = 4\ \text{V}$; $V_{DS} = 8\ \text{V}$; $I_D = 20\ \mu\text{A}$	–	2.0	V
$-V_{(P)G2-S}$	gate 2-source cut-off voltage	$V_{G1-S} = 0$; $V_{DS} = 8\ \text{V}$; $I_D = 20\ \mu\text{A}$	–	1.5	V
I_{DSS}	drain-source current	$V_{G2-S} = 4\ \text{V}$; $V_{DS} = 8\ \text{V}$; $V_{G1-S} = 0$; note 1	2	18	mA
$\pm I_{G1-SS}$	gate 1 cut-off current	$V_{G2-S} = V_{DS} = 0$; $V_{G1-S} = \pm 5\ \text{V}$	–	50	nA
$\pm I_{G2-SS}$	gate 2 cut-off current	$V_{G1-S} = V_{DS} = 0$; $V_{G2-S} = \pm 5\ \text{V}$	–	50	nA

Note

1. Measured under pulse condition.

DYNAMIC CHARACTERISTICS

Common source; $T_{amb} = 25\ ^\circ\text{C}$; $V_{DS} = 8\ \text{V}$; $V_{G2-S} = 4\ \text{V}$; $I_D = 10\ \text{mA}$.

SYMBOL	PARAMETER	CONDITIONS	MIN.	TYP.	MAX.	UNIT
$ y_{fs} $	forward transfer admittance	$f = 1\ \text{kHz}$	21	24	–	mS
C_{ig1-s}	input capacitance at gate 1	$f = 1\ \text{MHz}$	–	2.1	2.5	pF
C_{ig2-s}	input capacitance at gate 2	$f = 1\ \text{MHz}$	–	1.2	–	pF
C_{os}	output capacitance	$f = 1\ \text{MHz}$	–	1.05	–	pF
C_{rs}	reverse transfer capacitance	$f = 1\ \text{MHz}$	–	25	–	fF
F	noise figure	$f = 200\ \text{MHz}$; $G_S = 2\ \text{mS}$; $B_S = B_{Sopt}$	–	0.6	–	dB
		$f = 800\ \text{MHz}$; $G_S = 3.3\ \text{mS}$; $B_S = B_{Sopt}$	–	1.0	–	dB

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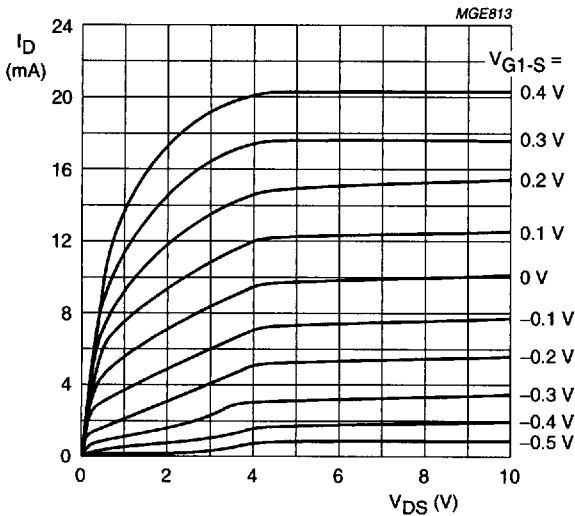


Fig.5 Output characteristics; typical values.

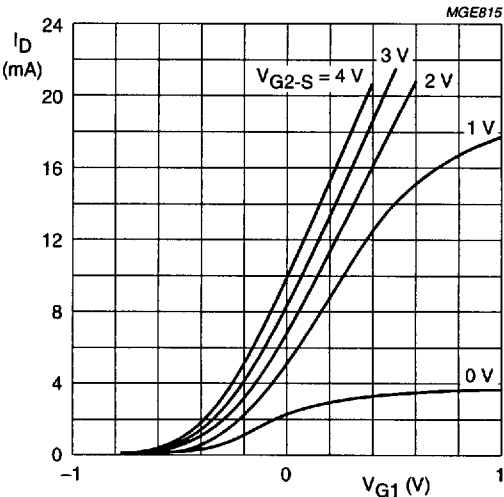


Fig.6 Transfer characteristics; typical values.

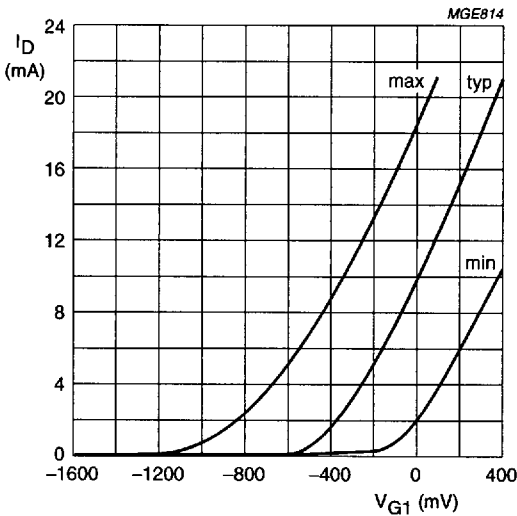


Fig.7 Drain current as a function of gate 1 voltage; typical values.

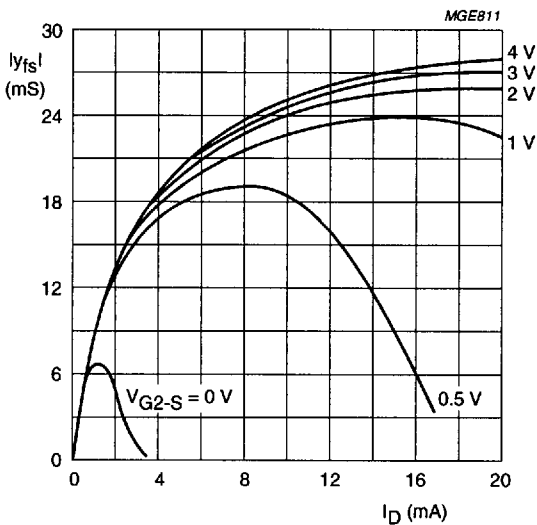


Fig.8 Forward transfer admittance as a function of drain current; typical values.

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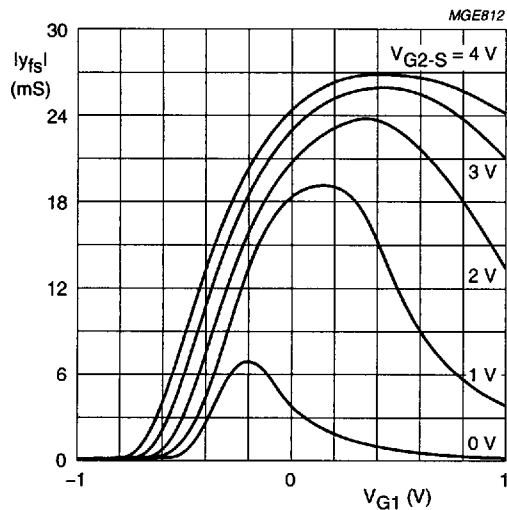
 $V_{DS} = 8$ V; $T_{amb} = 25$ °C.

Fig.9 Forward transfer admittance as a function of gate 1 voltage; typical values.

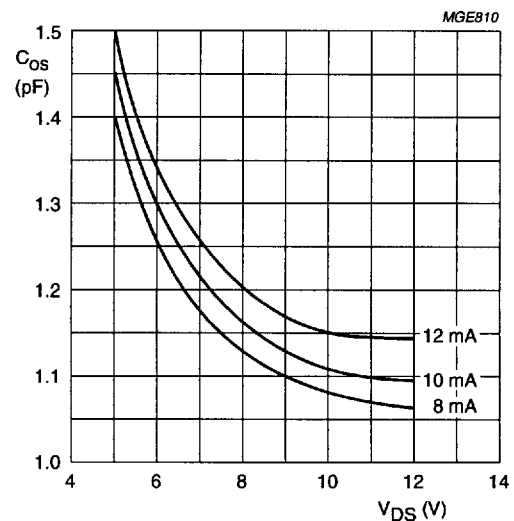
 $V_{G2-S} = 4$ V; $f = 1$ MHz; $T_{amb} = 25$ °C.

Fig.10 Output capacitance as a function of drain-source voltage; typical values.

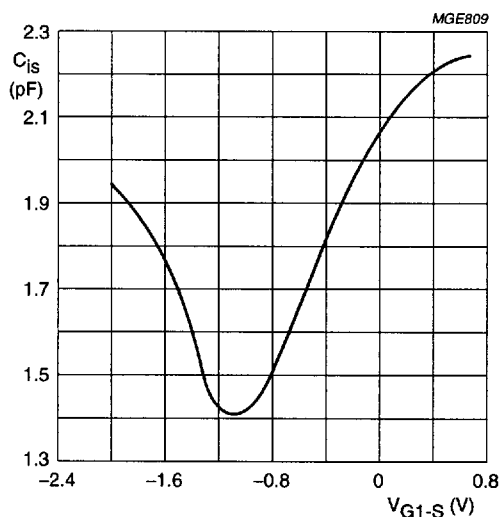
 $V_{DS} = 8$ V; $V_{G2-S} = 4$ V; $f = 1$ MHz; $T_{amb} = 25$ °C.

Fig.11 Gate 1 input capacitance as a function of gate 1-source voltage; typical values.

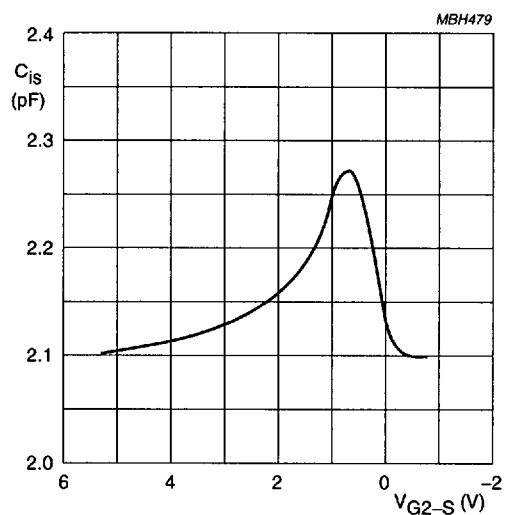
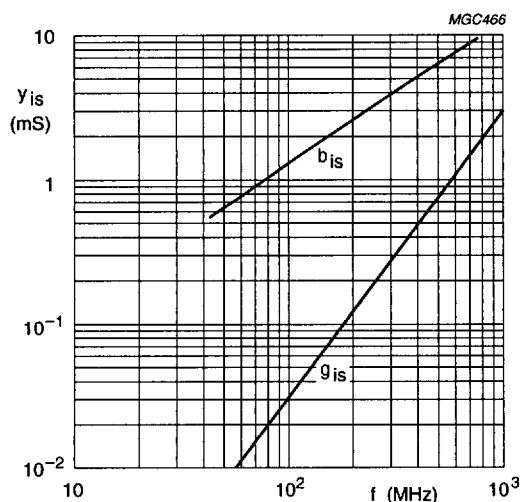
 $V_{DS} = 8$ V; $V_{G1-S} = 0$ V; $f = 1$ MHz; $T_{amb} = 25$ °C.

Fig.12 Gate 1 input capacitance as a function of gate 2-source voltage; typical values.

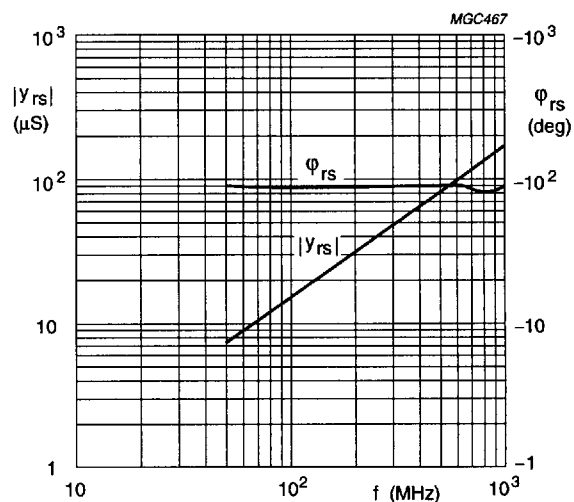
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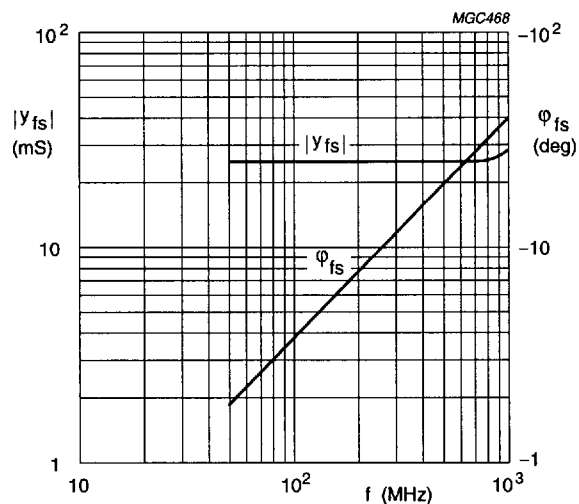
$V_{DS} = 8\text{ V}$; $V_{G2-S} = 4\text{ V}$; $I_D = 10\text{ mA}$; $T_{amb} = 25\text{ }^{\circ}\text{C}$.

Fig.13 Input admittance as a function of the frequency; typical values.



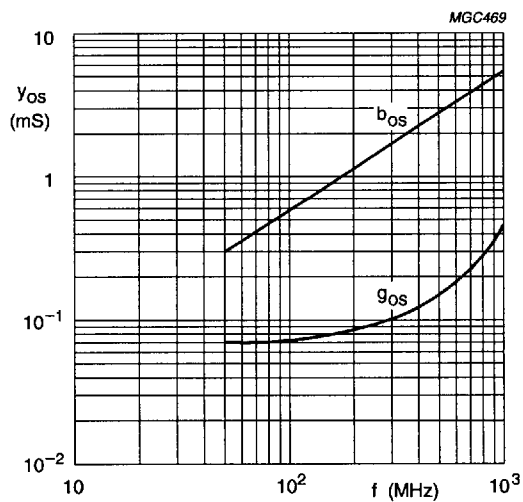
$V_{DS} = 8\text{ V}$; $V_{G2-S} = 4\text{ V}$; $I_D = 10\text{ mA}$; $T_{amb} = 25\text{ }^{\circ}\text{C}$.

Fig.14 Reverse transfer admittance and phase as a function of frequency; typical values.



$V_{DS} = 8\text{ V}$; $V_{G2-S} = 4\text{ V}$; $I_D = 10\text{ mA}$; $T_{amb} = 25\text{ }^{\circ}\text{C}$.

Fig.15 Forward transfer admittance and phase as a function of frequency; typical values.

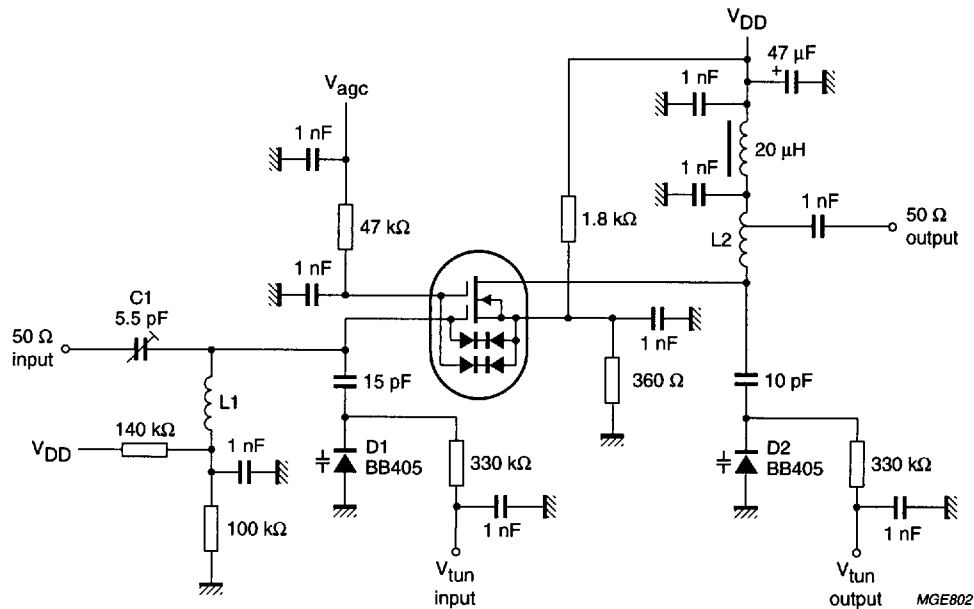


$V_{DS} = 8\text{ V}$; $V_{G2-S} = 4\text{ V}$; $I_D = 10\text{ mA}$; $T_{amb} = 25\text{ }^{\circ}\text{C}$.

Fig.16 Output admittance as a function of the frequency; typical values.

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$V_{DD} = 12\text{ V}$; $G_S = 2\text{ mS}$; $G_L = 0.5\text{ mS}$.

$L1 = 45\text{ nH}$; 4 turns 0.8 mm copper wire, internal diameter 4 mm.

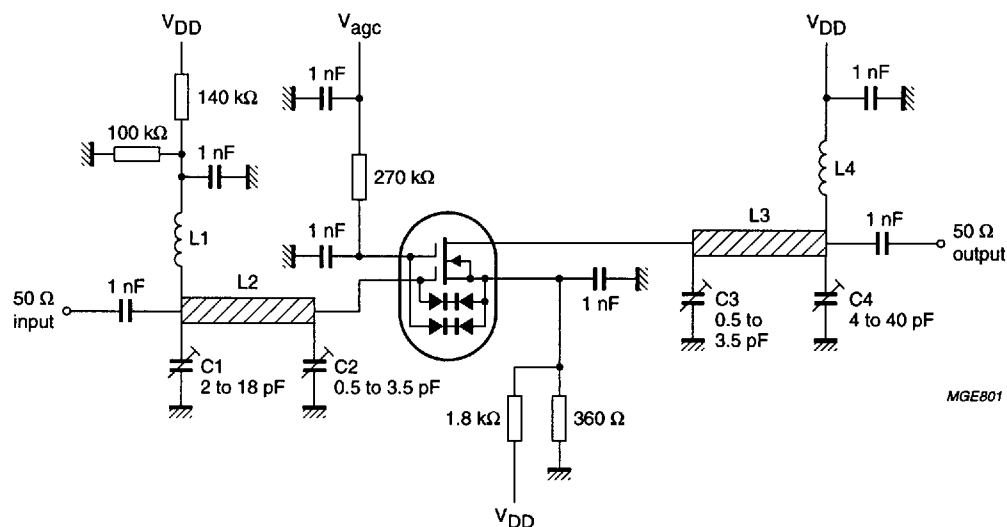
$L2 = 160\text{ nH}$; 3 turns 0.8 mm copper wire, internal diameter 8 mm.

Tapped at approximately half a turn from the cold side, to adjust $G_L = 0.5\text{ mS}$. $C1$ adjusted for $G_S = 2\text{ mS}$.

Fig.17 Gain control test circuit at $f = 200\text{ MHz}$.

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MGE801

$V_{DD} = 12\text{ V}$; $G_S = 3.3\text{ mS}$; $G_L = 1\text{ mS}$.

$L1 = L4 = 200\text{ nH}$; 11 turns 0.5 mm copper wire, without spacing, internal diameter 3 mm.

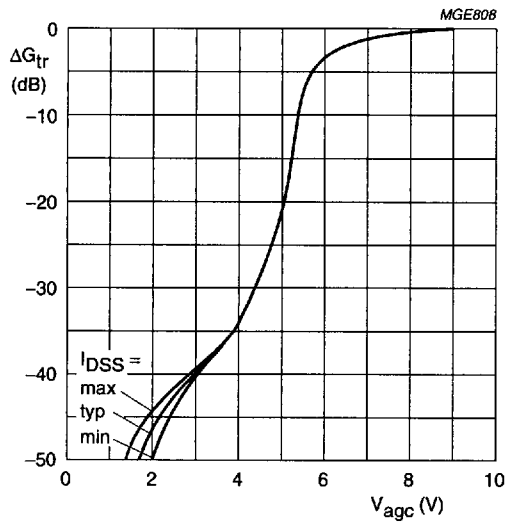
$L2 = 2\text{ cm}$, silvered 0.8 mm copper wire, 4 mm above ground plane.

$L3 = 2\text{ cm}$, silvered 0.5 mm copper wire, 4 mm above ground plane.

Fig.18 Gain control test circuit at $f = 800\text{ MHz}$.

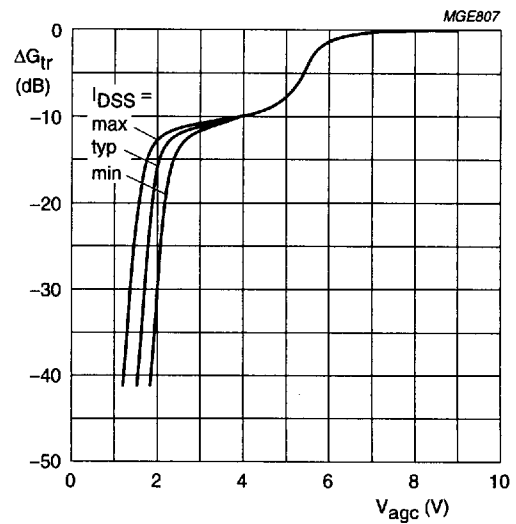
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$V_{DD} = 12$ V; $f = 200$ MHz; $T_{amb} = 25$ °C.

Fig.19 Automatic gain control characteristics measured in circuit of Fig.17.



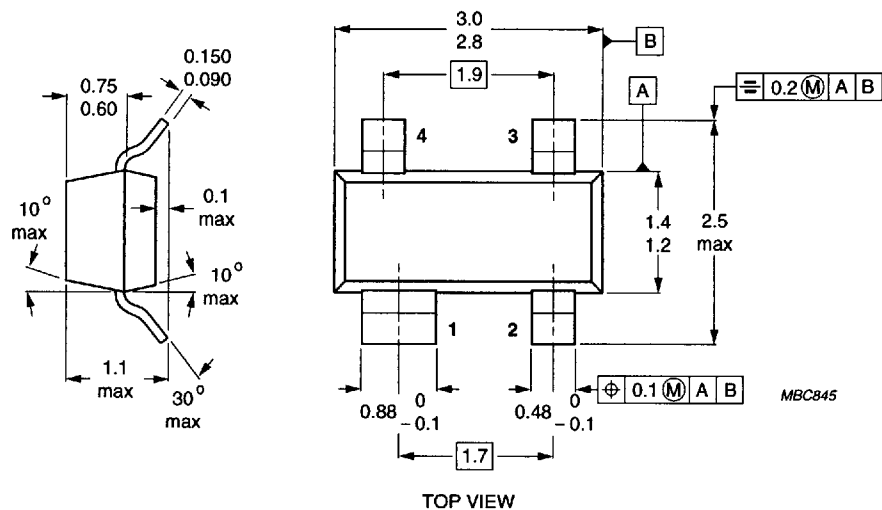
$V_{DD} = 12$ V; $f = 800$ MHz; $T_{amb} = 25$ °C.

Fig.20 Automatic gain control characteristics measured in circuit of Fig.18.

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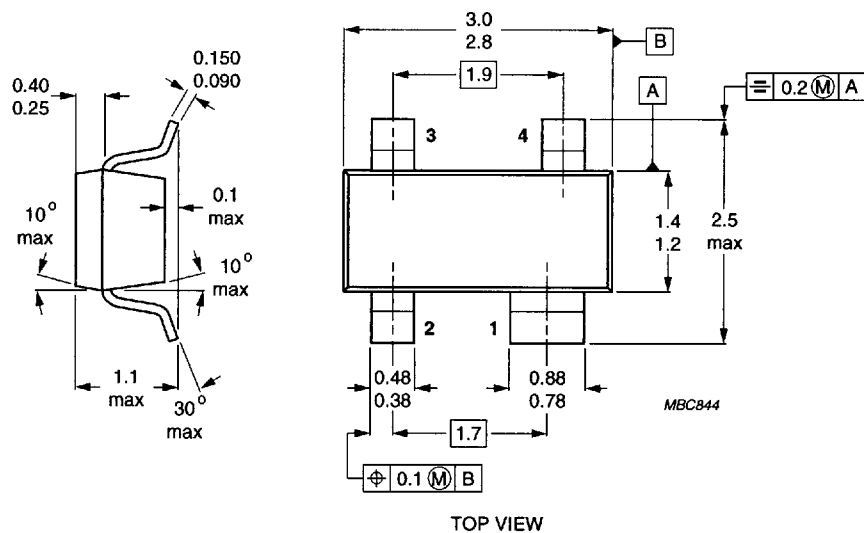
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PACKAGE OUTLINES



Dimensions in mm.

Fig.21 SOT143.



Dimensions in mm.

Fig.22 SOT143R.